

L Number	Hits	Search Text	DB	Time stamp
1	2	"20020086556"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 13:30
3	3477	((silicon adj monoxide) or SiO) near12 (source target evaporat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:12
4	182	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3))) and (((silicon adj monoxide) or SiO) near12 (source target evaporat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 14:49
5	3634	((silicon adj monoxide) or SiO) near15 (sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 14:49
6	5448	((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 14:50
7	16331	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:12
8	201	((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) same (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 14:53
9	16	((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) same (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 14:58
10	21	((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) and (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:13
11	5	((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) and (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) not (((silicon adj monoxide) or SiO) near15 (source target sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) same (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3 coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:01
12	354	204/298.26.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:01

13	5	((silicon adj monoxide) or SiO) and 204/298.26.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:11
14	60466	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:52
15	317	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:52
16	213	(((((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))) and @ad<20010104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:14
17	83	(((((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))) and @rlad<20010104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:14
18	230	(((((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))) and @ad<20010104) (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))) and @rlad<20010104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:14
19	1461	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:52
21	54	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) same (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:53
20	11	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:53
22	43	(((((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) same (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))) not (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:56